

## Body Effect:

Normally, Substrate and Source are connected (grounded)

But if Source is not grounded, the threshold voltage is not 1V. It follows the following equation

$$V_t = V_{t0} + \gamma \sqrt{V_{sb}}$$

Example:

If source terminal = 1V, Substrate = 0V,

$$\text{Then } V_t = V_{t0} + \gamma \sqrt{V_{sb}}$$

$$= 1 + 0.5 \sqrt{1 - 0}$$
$$= 1.5 \text{ V}$$

where  
 $V_{sb} = V_s - V_b$   
Source      Substrate

$\gamma = \text{constant}$   
 $= 0.3 \text{ to } 0.7$

2.4

## $I_{ds}$ vs $V_{ds}$ characteristics of NMOS

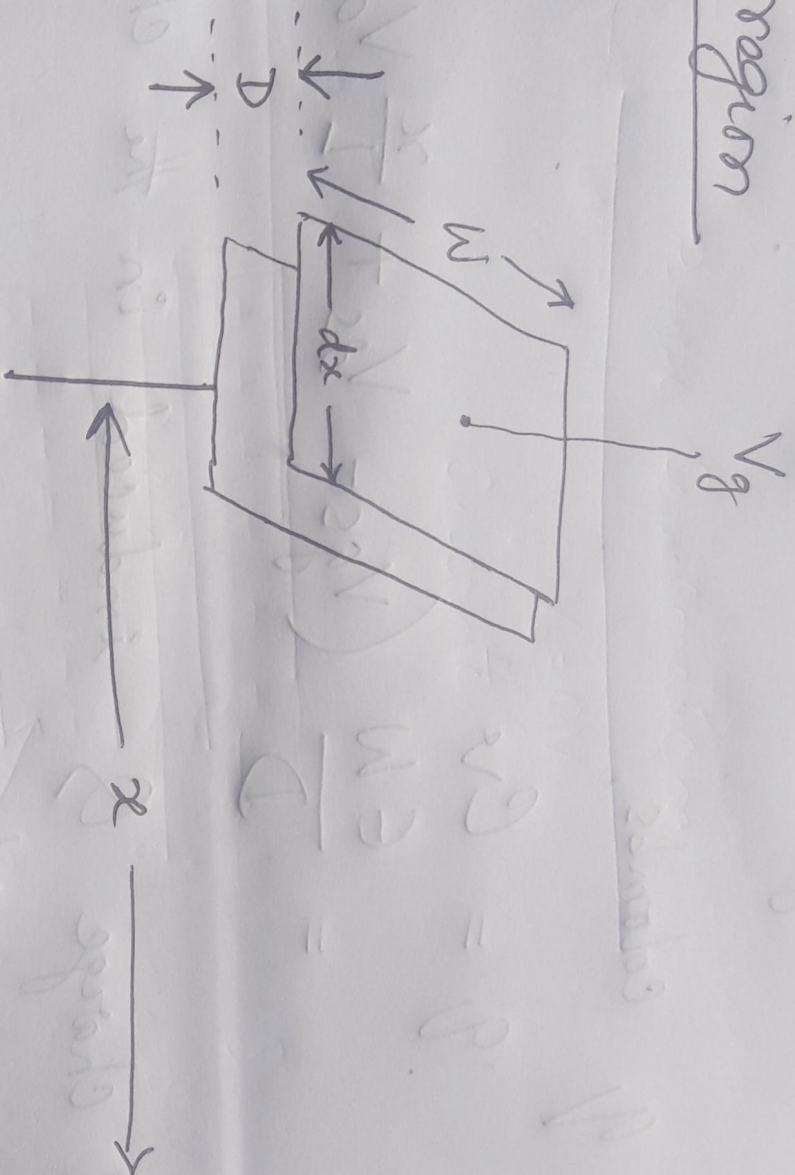
\* When  $V_{gs} < V_t$  the transistor (NMOS) is off.  
So no current flows (regardless of  $V_{ds}$ )

\* But if  $V_{gs} > V_t$ , NMOS conducts

- Resistive region, when  $V_{ds} < V_{gs} - V_t$
- Saturation region, when  $V_{ds} \geq V_{gs} - V_t$



# a) Resistive region



Source



The channel width =  $W$

length =  $L$

Depth =  $D$

Let us consider these capacitances of length  $dx$  situated at distance  $x$  from drain terminal.

$$C = \frac{\epsilon \cdot \text{Area}}{\text{Thickness}}$$

$$= \frac{\epsilon (W \cdot dx)}{D}$$

$\epsilon$  = Permittivity of insulator

The voltage  $V_0$  in excess of  $V_t$  across the capacitor is

$$V = \left( V_{gd} + \frac{x}{L} V_{ds} \right) - V_t$$

$$= V_{gs} - V_{ds} + \frac{x}{L} V_{ds} - V_t$$

Charge  $q$  coulombs,

$$q = C \cdot V$$

$$= \frac{\epsilon W}{D} \left( V_{gs} - V_{ds} + \frac{x}{L} V_{ds} - V_t \right) dx$$



So total charge  $Q$  induced in the channel is

$$\begin{aligned} Q &= \int_0^L \left( \frac{\epsilon W}{D} (V_{gs} - V_{ds} + \frac{x}{L} V_{ds} - V_t) \right) dx \\ &= \frac{\epsilon W}{D} (V_{gs} - V_{ds} - V_t) L + \frac{V_{ds}}{L} \left[ \frac{x^2}{2} \right]_0^L \\ &= \frac{\epsilon W}{D} (V_{gs} - V_{ds} - V_t) L + \frac{V_{ds}}{2} \times L \end{aligned}$$

$$\therefore Q = \frac{CWL}{D} \left( V_{gs} - V_{ts} - V_t + \frac{V_{ds}}{2} \right)$$

$$Q = \frac{CWL}{D} \left( V_{gs} - \frac{V_{ds}}{2} - V_t \right) \dots (1)$$

Again,  $Q = I_{ds} \times t$

$$t = \frac{\text{Channel Length, } L}{\text{electron velocity}}$$

$$= \frac{L}{\mu_n V_{ds}} = \frac{L^2}{\mu_n V_{ds}}$$

Putting the value of  $Q$  and  $t$

electron mobility

$$\mu_n = \frac{\text{electron velocity}}{\text{electric field}}$$

$$= \frac{\text{elec velocity}}{V_{ds}/L}$$

$\therefore \text{elec. velocity} = \frac{\mu_n V_{ds}}{L}$



Putting the value of  $Q$  and  $t$

$$\begin{aligned} I_{ds} &= \frac{Q}{t} = \frac{CWL}{D} \left( V_{gs} - \frac{V_{ds}}{2} - V_t \right) \times \frac{\mu_n V_{ds}}{L} \\ &= \frac{CWL\mu_n}{L \cdot D} \left( V_{gs} - \frac{V_{ds}}{2} - V_t \right) V_{ds} \end{aligned}$$

$$\therefore I_{ds} = \frac{C\mu_n WL}{D} \times \left[ \left( V_{gs} - V_t \right) V_{ds} - \frac{V_{ds}^2}{2} \right]$$

Resistive region Current